

### Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of the claims in the application:

### Listing of Claims:

1. (Currently Amended) A chemical vapor deposition system comprising: a ~~cleaning first~~ gas source ~~configured to generate a reactive cleaning gas; and fluidly coupled to~~ a chemical vapor deposition chamber ~~including a processing gas shower, a cleaning through a first~~ gas distribution channel ~~disposed within a lid of the chemical vapor deposition chamber, the lid further supporting a shower head disposed within the chemical vapor deposition chamber and~~ separate from the ~~processing gas shower first~~ gas distribution channel, ~~and said lid having an interior rim including~~ a plurality of cleaning gas injection ports ~~each of which is~~ fluidly connected to the ~~cleaning first~~ gas distribution channel, ~~and disposed and various ones of which are oriented at different angles with respect to introduce the cleaning gas into an interior of a wall of the chemical vapor deposition chamber, said wall being attached to said lid.~~

2 - 4. (Cancelled)

5. (Currently Amended) The chemical vapor deposition system of claim 1, wherein the plurality of cleaning gas injection ports include a first subset of the plurality of cleaning gas injection ports disposed at a first angle relative to ~~side walls the interior of the wall~~ of the chemical vapor deposition chamber, and a second subset of the plurality of cleaning gas injection ports disposed at a second angle relative to the ~~side walls the interior of the wall~~.

6. (Cancelled)

7. (Currently Amended) The chemical vapor deposition system of claim 1, further including internal plumbing ~~configured to transport the reactive cleaning gas to coupling the cleaning first~~ gas distribution channel ~~to the first gas source, the internal plumbing being disposed within a the wall of the chemical vapor deposition chamber.~~

8. (Currently Amended) The chemical vapor deposition system of claim 1, further including a plurality of channel openings ~~configured for reactive cleaning gas to enter coupling the internal plumbing to the~~ cleaning gas distribution channel.

9. (Currently Amended) The chemical vapor deposition system of claim 1, further including a chamber collar ~~configured to separate a~~ separating the lid of the chemical vapor deposition chamber from ~~walls of the chemical vapor deposition chamber, the chamber collar wall and~~ including internal plumbing ~~configured to supply reactive cleaning gas to~~ coupling the cleaning gas distribution channel to the first gas source.

10 - 21. (Cancelled)